

Preface

The 10th International Symposium on Plasma Chemistry, a IUPAC sponsored conference held regularly every two years since 1973, was originally planned to take place in Jerusalem, Israel. For safety reasons, the Israeli organizers asked the International Organizing Committee to choose another location for the Symposium. The IOC decided in November 1990 to move the 10th ISPC from Jerusalem to Bochum, but to keep the envisaged date unchanged.

The local organizers in Bochum were then faced with the problem of setting up an international conference of renown and tradition within one third of the usual span of time. The problem was solved with enthusiasm and with the support and encouragement from many sides.

The success of a scientific symposium cannot be measured by statistical figures. Nevertheless, these figures looked favorable to the organizers: More than 450 participants from over 30 countries were counted. 396 accepted contributions were presented from 29 countries, including 4 plenary lectures, 24 invited topical lectures, 110 oral and 258 poster presentations. Next to the participants from Germany, the delegations from France, Japan, USSR, USA, the Netherlands, Italy and Canada were the largest.

Similar to previous practice, the 10th ISPC was held in three - mostly parallel - sessions with the following topics:

1. Thermal Plasma
 - 1.1 Modelling and Plasma Generation
 - 1.2 Diagnostics of Thermal Plasmas
 - 1.3 Plasma-Substrate Interaction
 - 1.4 Materials Processing
 - 1.5 Chemical and Metallurgical Processing
2. Low Pressure Plasma
 - 2.1 Modelling and Diagnostics of Low Pressure Plasmas
 - 2.2 Plasma Substrate Interaction
 - 2.3 Materials Synthesis and Polymerization
 - 2.4 Inorganic and Hard Coatings
 - 2.5 Surface Characterization
3. Special Topics
 - 3.1 Diamond and Diamond-Like Coatings
 - 3.2 Low Temperature Atmospheric Pressure Plasma Chemistry

Session 2.4 "Inorganic and Hard Coatings" was dedicated to the memorial of Prof. Yves Catherine, who died the 2nd of June, 1991.

This issue of "Pure and Applied Chemistry" contains the plenary and invited topical lectures in the sequence of the topics listed above.

- Klaus Wiesemann -

(Symposium Editors)

- Dieter Neuschütz -